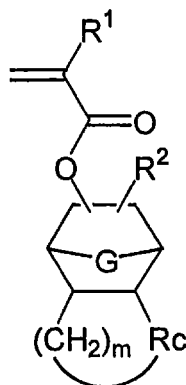


ABSTRACT
MONOMER FOR CHEMICAL AMPLIFIED PHOTORESIST COMPOSITIONS

The present invention discloses a compound having the following formula (I),



(I)

wherein R¹ is H, haloalkyl group or C₁-C₄ alkyl group; R² is hydroxyl group, C₁-C₈ alkoxy group or C₁-C₈ thioalkyl group; G is (CH₂)_n, O or S, wherein n is 0, 1, 2, 3 or 4; Rc is a lactone group; and m is 1, 2 or 3. This compound is a monomer and suitable for synthesis to form polymers with good hydrophilicity, adhesion and dry-etch resistance. Particularly, this compound can form photosensitive polymers or copolymers by reacting with suitable photosensitive monomers.



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